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Dated: October 21, 2004      Signature: (Michael R. Hill)

Docket No.: 30205/39509  
(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of:  
Cheol-Kyu Bok et al.

Application No.: 10/722,815

Art Unit: 1752

Filed: November 26, 2003

Examiner: Amanda C. Walke

For: **OVERCOATING COMPOSITION FOR  
PHOTORESIST AND METHOD FOR  
FORMING PHOTORESIST PATTERN USING  
THE SAME**

**AMENDMENT IN RESPONSE TO NON-FINAL OFFICE ACTION**

MS Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

**INTRODUCTORY COMMENTS**

Please enter the following amendment in the above-referenced patent application.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** in support of the allowability of this application begin on page 6 of this paper.